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(54) **Title:** LOW NUMERICAL APERTURE ALIGNMENT

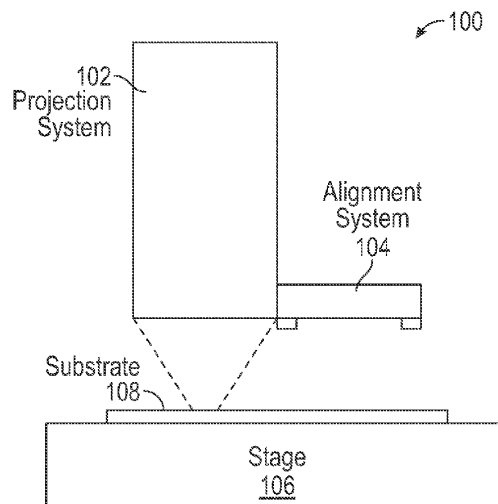


FIG. 1A

(57) **Abstract:** Disclosed herein are examples of a photolithography machine with fast alignment. The machine may include a stage to hold and move a substrate and a projection system to project images on a plurality of exposure regions of the substrate. The machine may also include an alignment system positioned adjacent to the projection system. The alignment system may include a plurality of microscope cameras with a fixed focus, each microscope camera configured to detect a respective fiducial in a respective exposure region of the substrate

[Continued on next page]

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